

SOI Nanophotonic Baseline Process

AMO offers research, development and small scale production of silicon nanophotonic devices and circuits. AMO's advanced baseline processes cover a wide range from single passive nanophotonic chips up to 6" wafer processing with active nanophotonic devices and two-level metal interconnects.

Frequently requested photonic components include the following structures:

Schematic drawing of an active silicon nanophotonic ring resonator modulator with heating elements and metal interconnects:

Photonic Components Waveguides Processes for strip, ridge, slotted and combined technology waveguides Passive Devices Processes for ring resonators, splitters, couplers, photonic crystals, etc. Active Devices Processes for n+ and p+ doping and metal interconnects Heater Technology Processes for integrated micro heaters based on titanium Fiber-Chip Coupling Processes for grating couplers and mode-size converters **Peripheric Structures** Processes for patterned top cladding, membrane etching, metal integration

2nd metal layer 2nd oxide layer 1st metal layer

1st oxide layer

implantation

SOI chip

AMO offers

Individual Service	 for high lexibility and short turnaround
Combination of Electron Beam and Photolithography	 for high throughput and ultra-high alignment accuracy
Flexibility	 from single chip to wafer batch processing
IP Protection guaranteed	 flexible IP protection schemesadapted to customers' needs
Modes of Cooperation	• direct • subcontractor • project partner



Contact

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